

The present invention relates to a multibeam exposure head having a multibeam light source which exposes a recording material by main scanning. Herein, the multibeam light source has a first multiple beam forming light source in which a plurality of beam emitting ports are arranged parallel to each other while being spaced apart from each other by a predetermined distance, and a second multiple beam forming light source in which a plurality of beam emitting ports are arranged parallel to each other being spaced apart from each other by the predetermined distance.